

SEMICONDUCTOR HEAT TREATMENT DEVICE AND METHOD FOR CONTROLLING PRESSURE IN PROCESS CHAMBER

ABSTRACT

The present disclosure provides a semiconductor heat treatment device and a method of controlling a pressure in a process chamber thereof, which involves the technical field of semiconductor processing technology. The control method includes: obtaining an actual pressure value in the process chamber; determining a first valve opening value for controlling opening an exhaust valve according to a difference between the actual pressure value and a preset target pressure value; determining a first valve opening change value according to the first valve opening value and a current valve opening value; determining whether the first valve opening change value is within a preset fluctuation range of a valve opening change value corresponding to a current process stage; and in response to the first valve opening change value being within the fluctuation range, adjusting opening of an exhaust valve according to the first valve opening value. The control method solves the problem of substantial pressure fluctuation in the process chamber of the semiconductor heat treatment device.

FIG.2